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**Aaron Scott Lukas, et al.**

FILING DATE

GROUP

(37 CFR 1.98(b))

**U.S. PATENT DOCUMENTS**

EXAM- INER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	4 6 0 3 1 6 8	7/29/1986	S. Sasaki, et al.	522	18	2/19/1985
	5 6 0 9 9 2 5	3/11/1997	R. C. Camilletti, et al.	427	503	12/4/1995
	5 9 7 0 3 8 4	10/19/1999	S. Yamazaki, et al.	438	795	8/2/1995
	6 0 1 7 8 0 6	1/25/2000	K. C. Harvey	438	475	7/28/1998
	6 0 4 2 9 9 4	3/28/2000	J. Yang, et al.	430	296	1/8/1999
	6 1 6 8 9 8 0	1/2/2001	S. Yamazaki, et al.	438	162	9/26/1996
	6 2 8 4 0 5 0	9/4/2001	J. Shi, et al.	118	715	5/18/1998
01	0 0 3 8 9 1 9	11/8/2001	I. L. Berry, III, et al.	428	446	3/19/2001
02	0 1 0 2 4 1 3	8/1/2002	Q. Han, et al.	428	446	7/16/2001
02	0 1 0 6 5 0 0	8/8/2002	R. Albano, et al.	428	304.4	9/14/2001
02	0 1 4 2 5 8 5	10/3/2002	R. P. Mandal	438	633	3/4/2002
03	0 0 3 2 3 0 0	2/13/2003	C. Waldfried, et al.	438	725	5/14/2001
03	0 0 5 4 1 1 5	3/20/2003	R. Albano, et al.	427	487	9/14/2001

**FOREIGN PATENT DOCUMENTS**

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
					YES	NO
WO 9 7 0 0 5 3 5		World			X	
WO 02 0 6 5 5 3 4		World			X	

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

	E. G. Parada, et al., "Improvement of Silicon Oxide Film Properties by Ultraviolet Excimer Lamp Annealing," Applied Surface Science 86, pp. 294-298 (1995).
	A. Guo, et al., "Highly Active Visible-Light Photocatalysts for Curing a Ceramic Precursor <sup>1</sup> ," Chem Mater. 10, pp. 531-536 (1998).
	T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported, Mesoporous Thin Films," Chem. Mater. 12, pp. 3879-3884 (2000).
	M. Brinkmann, et al., "Room-Temperature Synthesis of a-SiO <sub>2</sub> Thin Films by UV-Assisted Ozonolysis of a Polymer Precursor," Chem. Mater. 13, pp. 967-972 (2001).
	A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesostructured Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light," Chem. Mater. 12, pp. 3842-3847 (2000).
	M. Ouyang, et al., "Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes," Chem. Mater. 12, pp. 1591-1596 (2000).
	Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.
	C. Waldfried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

EXAMINER

DATE CONSIDERED

**EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.**